



# NBTI-Resilient Memory Cells with NAND Gates for Highly-Ported Structures

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# Motivation



One of the main **sources of failure** affecting transistors:

- **NBTI** (Negative Bias Temperature Instability)

NBTI issues

- Affects **PMOS transistors with "0" at their gates**
- Some molecules are broken and some atoms displaced

NBTI negative effects

- $V_{TH}$  increases, and hence, PMOS transistors **become slower**
- Minimum operating voltage ( $V_{min}$ ) of bit cells in a given block increases, so  **$V_{DD}$  cannot be decreased** as much for power savings (e.g. UL1 cache)

# Agenda



Motivation

## **NBTI effects**

Memory cell design: conventional vs NAND-based

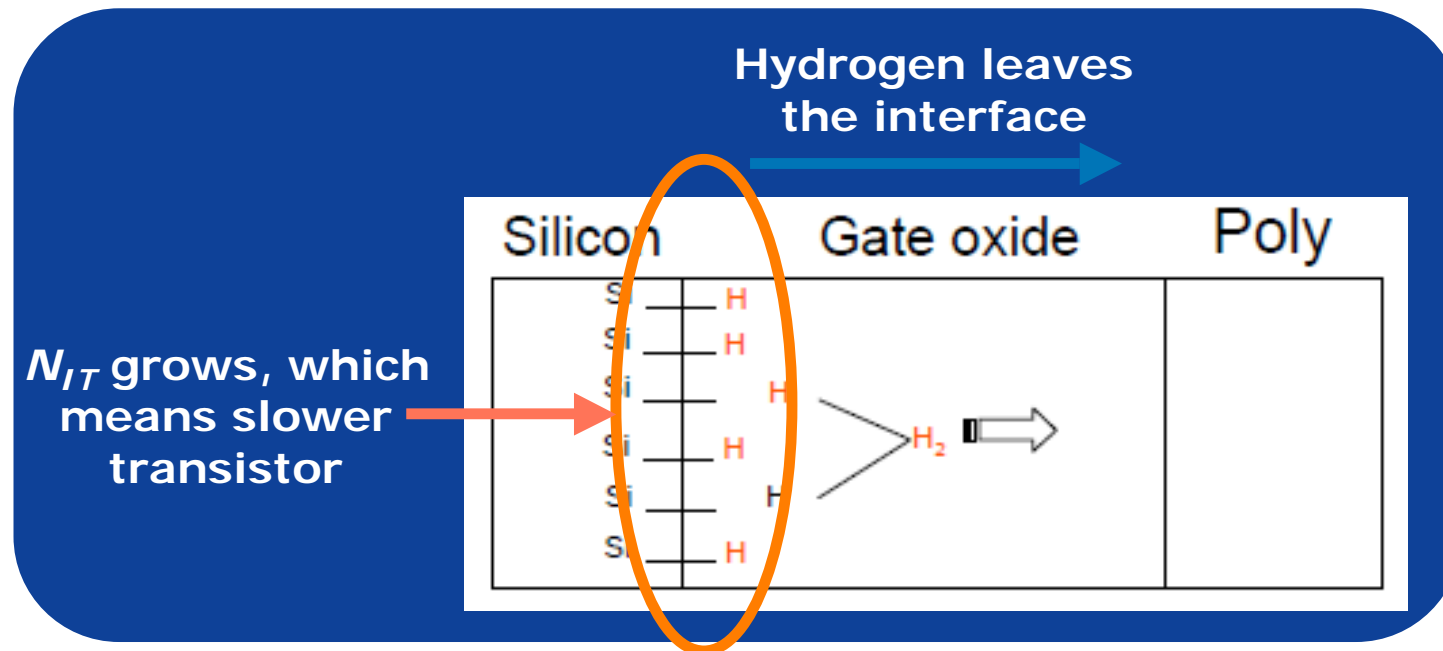
Results and final remarks

# NBTI Degradation



NBTI affects PMOS transistors when voltage at the gate is negative: Si-H bonds break

- More traps ( $N_{IT}$ ) in the interface make the transistor slower



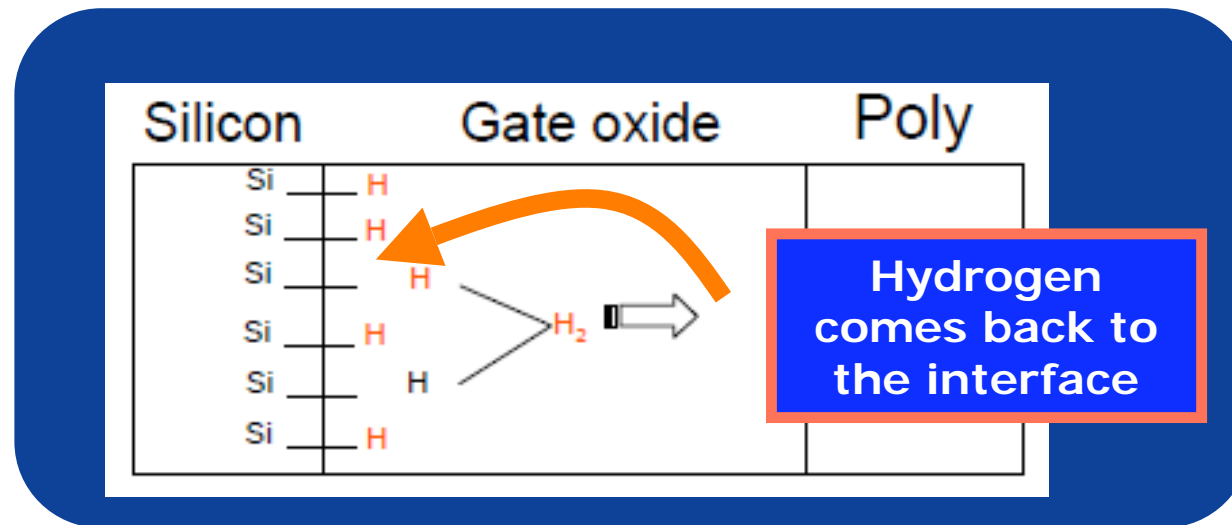
Source: M.A. Alam, "On Reliability of Microelectronic Devices: An Introductory Lecture on Negative Bias Temperature Instability", Sept. 2005

# NBTI Self-Healing



Self-healing during non-negative voltage at gate

- H, H<sup>+</sup>, H<sub>2</sub><sup>+</sup> close to the Si rebuild their bonds
- Self-healing is partial (not all bonds are rebuilt)



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# Agenda



Motivation

NBTI effects

**Memory cell design: conventional vs NAND-based**

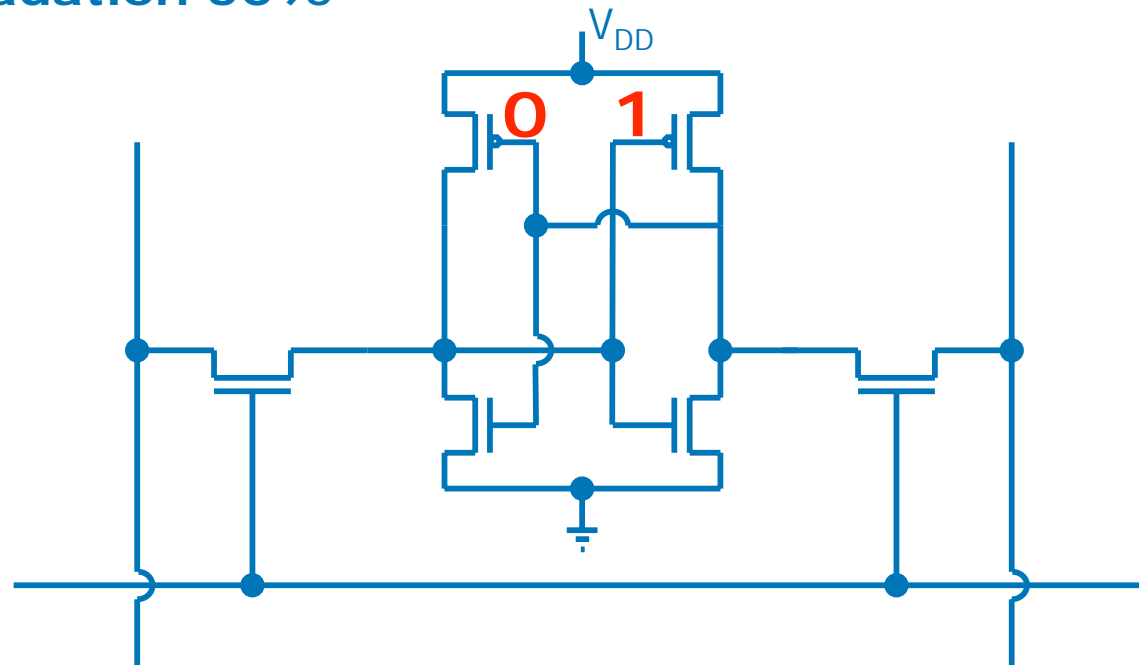
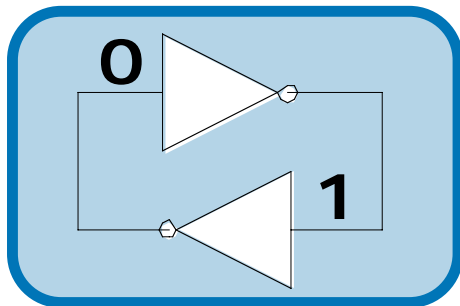
Results and final remarks

# Conventional Memory Cell Design



PMOS transistors degrade only when they have a “0” at their gates (what we call “duty cycle”)

- Two inverters. **One of them degrades at any time**
- Average **PMOS** degradation 50%

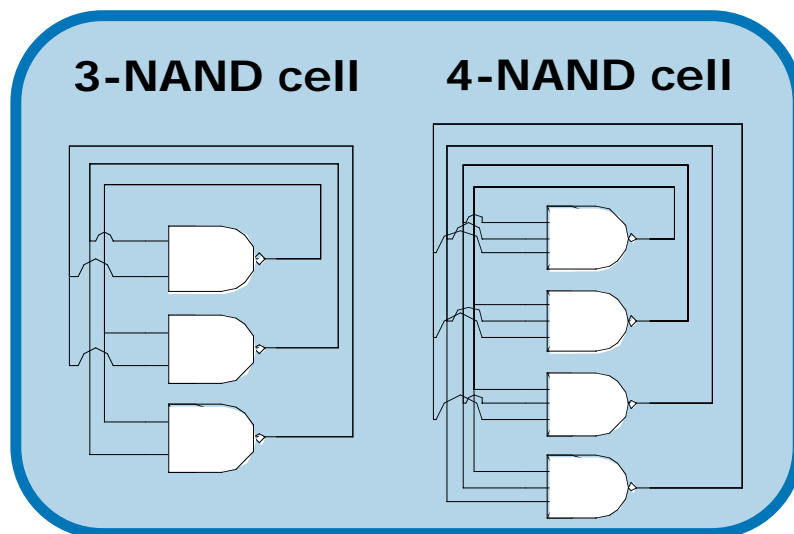


# New Memory Cell Design



## NAND-based memory cells

- A given number (N) of NANDs. Only **one NAND outputs a “0”**
- Average PMOS **degradation 1/N** (e.g. **N=4, degradation 25%**)
- Area overhead pays off for highly ported structures (e.g. register files)



### Example: 4-NAND cell

- Twice the number of bitlines than a conventional memory cell
- 4 different states, so **it encodes 2 bits**
- Thus, **same overhead per port** as a conventional memory cell



# Data Bias



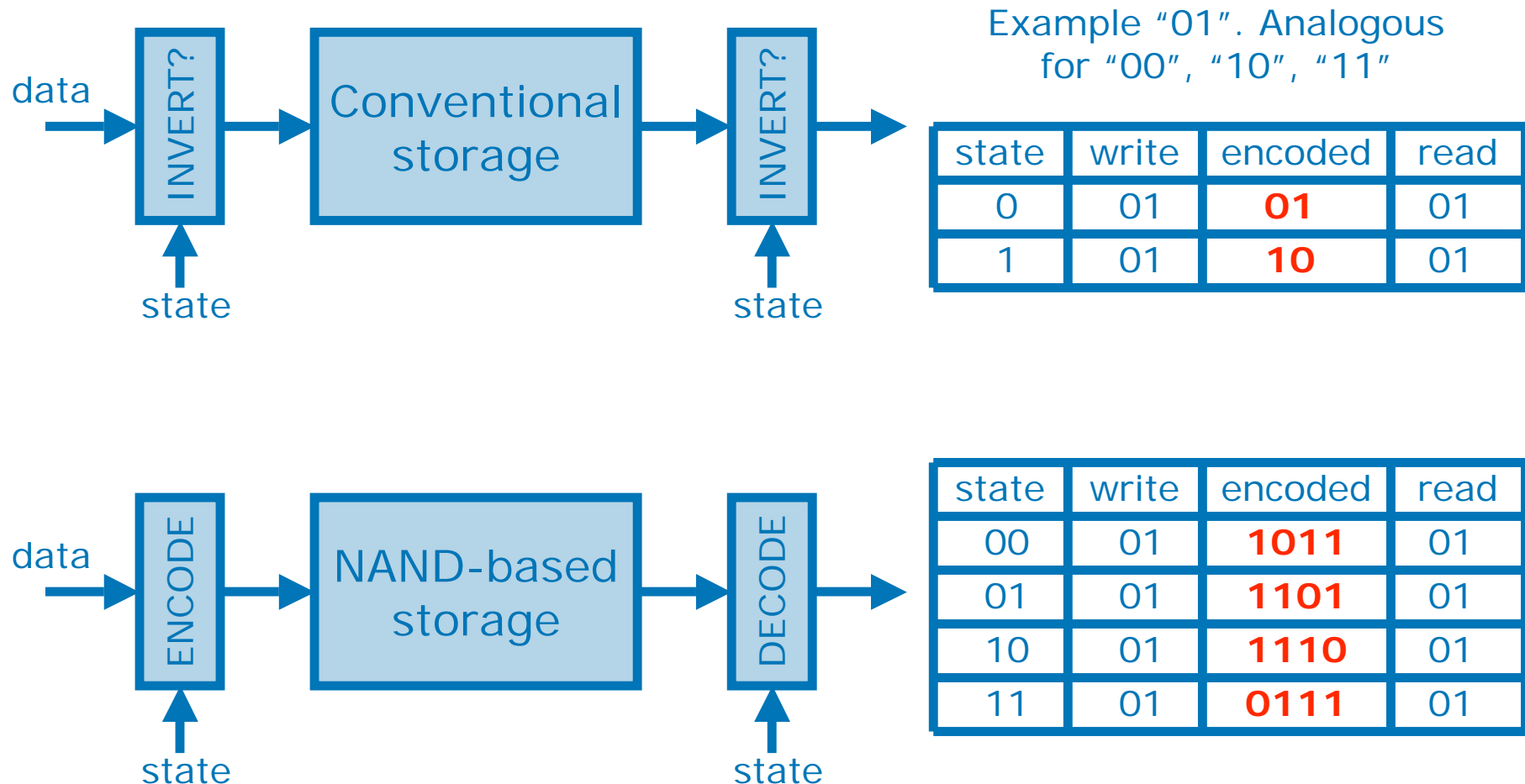
Data **highly biased** towards “0”

- Conventional cells: **One PMOS degrades much more** than the other
- NAND-based cells: **Some PMOS degrade much more** than the others

## Solution

- Conventional cells: **store inverted contents 50% of the time**
- NAND-based cells: **periodically change codification** of data to balance degradation of PMOS

# Example: Conventional vs 4-NAND



# Agenda



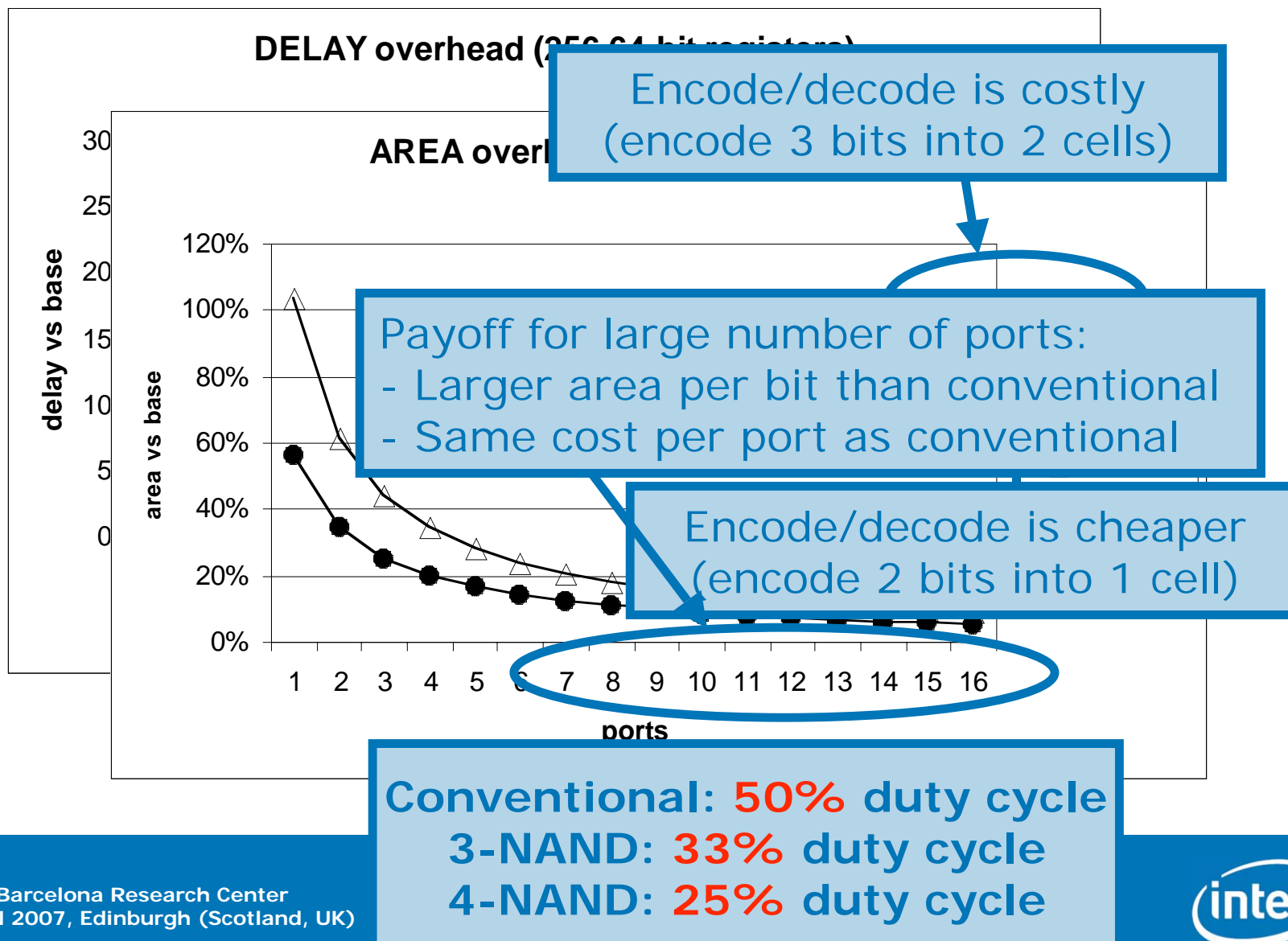
Motivation

NBTI effects

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**Results and final remarks**

# Preliminary Results



# Final Remarks



- NAND-based cells **reduce duty cycle** so lower guardbands are required for the **cycle time** and the **V<sub>min</sub>**
- Decreasing guardbands may **offset overheads** (partially or totally?)
- **Test chip data required**
  - Obtain accurate results of the overheads
  - Measure whether NAND-based cells payoff for current technologies
- NBTI degradation is still an open research topic
  - **How much does it cost** for current technologies? Different works show large discrepancies
  - **Will it worsen** for future technologies?



**Thank you !**